

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Atty. Docket

RENE MONSHOUWER ET AL

NL 000770

Serial No.

Filed: CONCURRENTLY

METHOD OF MEASURING ALIGNMENT OF A SUBSTRATE WITH RESPECT TO
A REFERENCE ALIGNMENT MARK

Commissioner for Patents
Washington, D.C. 20231

PRELIMINARY AMENDMENT

Sir:

Prior to calculation of the filing fee and examination,
please amend the above-identified application as follows:

IN THE SPECIFICATION

Page 21, in the paragraph beginning on line 9,

/ With an off-axis alignment-measuring device, for example that of Fig. 8, not only the position of a substrate but also the position of the substrate holder or substrate table can be measured. To this end, the holder or table is also provided with an alignment mark similar to the global substrate alignment mark. If the position of the substrate holder with respect to the reference in the alignment-measuring device has been determined, the position of the substrate mark with respect to the substrate holder mark will be known. To be able to determine the mutual position of the mask pattern and the substrate, a further measurement is necessary, namely that of the position of the mask pattern with respect to the substrate holder or table. For this